

Replacement Claims

56. (Amended) The method according to claim 55, further comprising modeling one or more additional anti-reflective coating layers, modeling the reflective properties of said additional anti-reflective layers in the lithography modeling program during all reflective modeling steps c, evaluating the reflective properties of said additional anti-reflective layers during all evaluating steps d, and adjusting the thicknesses, indices of refraction, and absorptions of said additional anti-reflective layers during all adjusting steps e.

57. (Amended) The method according to claim 55, further comprising modeling one or more additional reflective layers and modeling the reflective properties of said additional reflective layers in the lithography modeling program during all reflective modeling steps c.